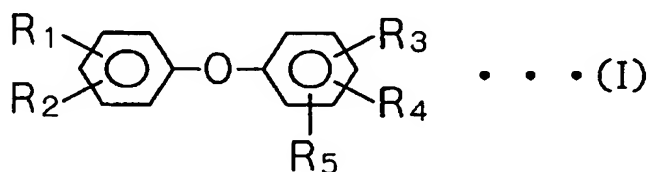


## ABSTRACT

To provide a developer composition for resists, capable of improving dimensional controllability of a resist pattern. The developer composition for resists comprises an organic quaternary ammonium base as a main component, said developer composition further comprising an anionic surfactant represented by the following general formula (I), and  $\text{SO}_4^{2-}$ , the content of  $\text{SO}_4^{2-}$  being from 0.01 to 1% by mass.



In the formula, at least one of  $\text{R}_1$  and  $\text{R}_2$  represents an alkyl or alkoxy group having 5 to 18 carbon atoms and the other one represents a hydrogen atom, or an alkyl or alkoxy group having 5 to 18 carbon atoms, and at least one of  $\text{R}_3$ ,  $\text{R}_4$  and  $\text{R}_5$  represents an ammonium sulfonate group or a sulfonic acid-substituted ammonium group and the others represent a hydrogen atom, an ammonium sulfonate group or a sulfonic acid-substituted ammonium group.